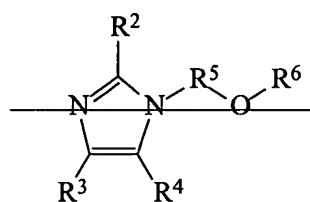


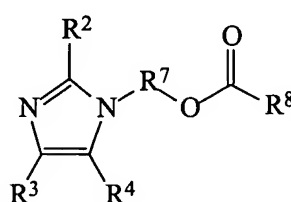
AMENDMENTS TO THE CLAIMS

1. (Cancelled).

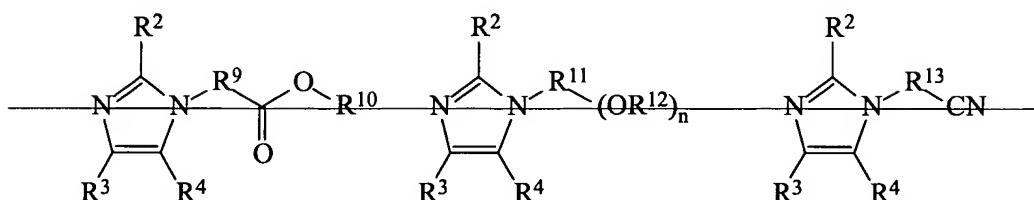
2. (Original) A resist composition comprising at least one basic compound represented by the general formula (3) formulae (2) to (6):



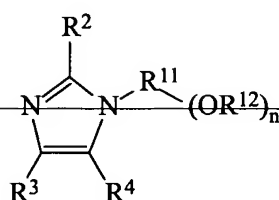
—(2)—



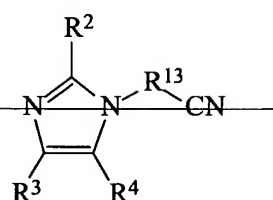
(3)



—(4)—



—(5)—



—(6)—

wherein R^2 , R^3 and R^4 are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

~~R^5 , R^7 , R^9 and R^{13} are each independently~~ R^7 is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; and

~~R^6 and R^8 are each independently~~ R^8 is a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups;

~~R¹⁰ is an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups;~~

~~R¹¹ is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 2 to 10 carbon atoms;~~

~~R¹² is each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups, or two of R¹² may bond together to form a ring; and n is equal to 2, 3, 4 or 5.~~

3. (Currently Amended) A positive-working resist composition comprising:

(A) the basic compound of claim 2 ~~claim 1~~;

(B) an organic solvent;

(C) a base resin having an acid labile group-protected acidic functional group which is alkali-insoluble or substantially alkali-insoluble, but becomes alkali-soluble when the acid labile group is eliminated; and

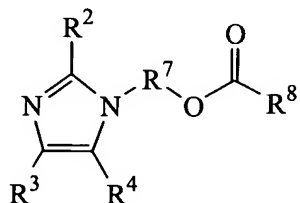
(D) a photoacid generator.

4. (Original) The positive resist composition of claim 3 which further comprises (E) a dissolution inhibitor.

5. (Currently Amended) A negative-working resist composition comprising:
- (A) the basic compound of claim 2 ~~claim 1~~;
 - (B) an organic solvent;
 - (C') a base resin which is alkali-soluble, but becomes substantially alkali-insoluble when crosslinked with a crosslinking agent;
 - (D) a photoacid generator; and
 - (F) a crosslinking agent which induces crosslinkage under the action of an acid.
6. (Original) A patterning process comprising the steps of:
- (1) applying the positive resist composition of claim 3 onto a substrate;
 - (2) heat treating the applied resist, then exposing the heat-treated resist through a photomask to high-energy radiation having a wavelength of at most 300 nm or an electron beam; and
 - (3) heat treating the exposed resist, then developing the resist with a liquid developer.
7. (Original) A patterning process comprising the steps of:
- (1) applying the negative resist composition of claim 5 onto a substrate;
 - (2) heat treating the applied resist, then exposing the heat-treated resist through a photomask to high-energy radiation having a wavelength of at most 300 nm or an electron beam; and
 - (3) heat treating the exposed resist, then developing the resist with a liquid developer.

8. (Cancelled).

9. (Withdrawn) A basic compound represented by the general formula (3):



(3)

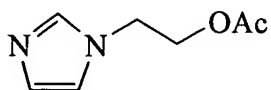
wherein R², R³ and R⁴ are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

R⁷ is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; and

R⁸ is a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups.

10-12. (Cancelled).

13. (Currently Amended) A compound of the formula:



Amine 37

14. (Withdrawn) A resist composition comprising the compound of claim 13.